

# Wafer scale production of graphene: opportunities and challenges

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[www.hvm-uk.com](http://www.hvm-uk.com)

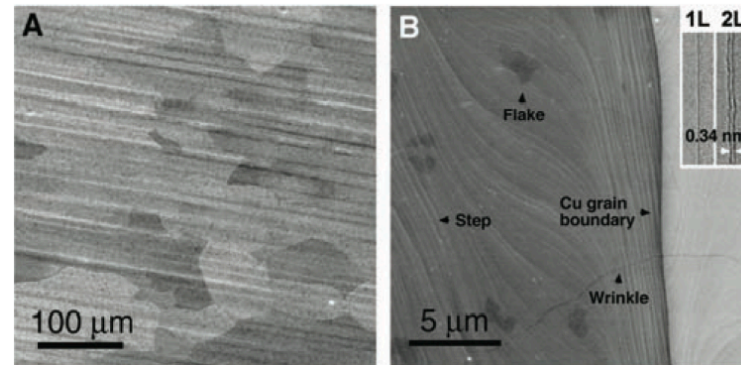
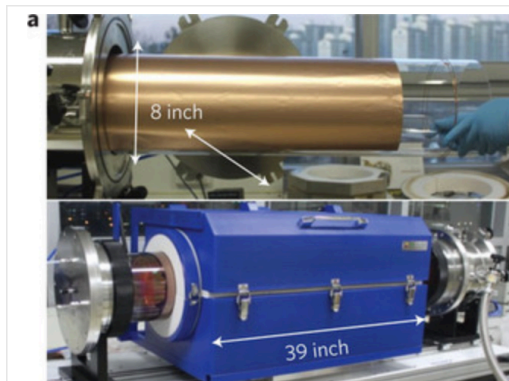
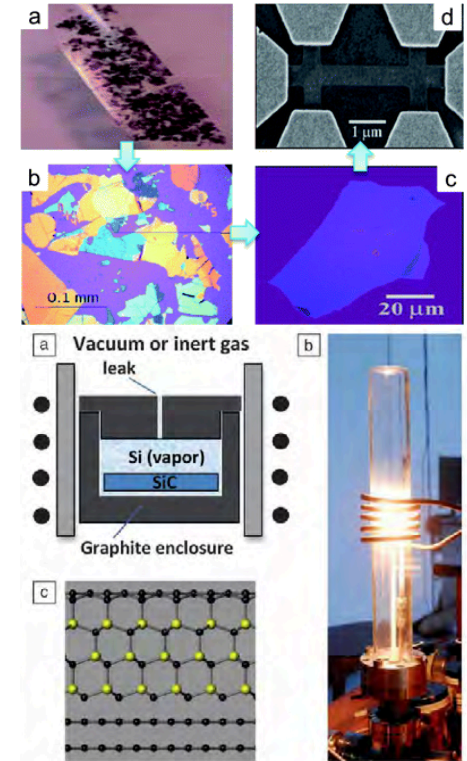
# Who are we

- Applied Nanolayers BV
  - Company building a 200 mm CVD wafer production line for graphene in The Netherlands.



# Production methods

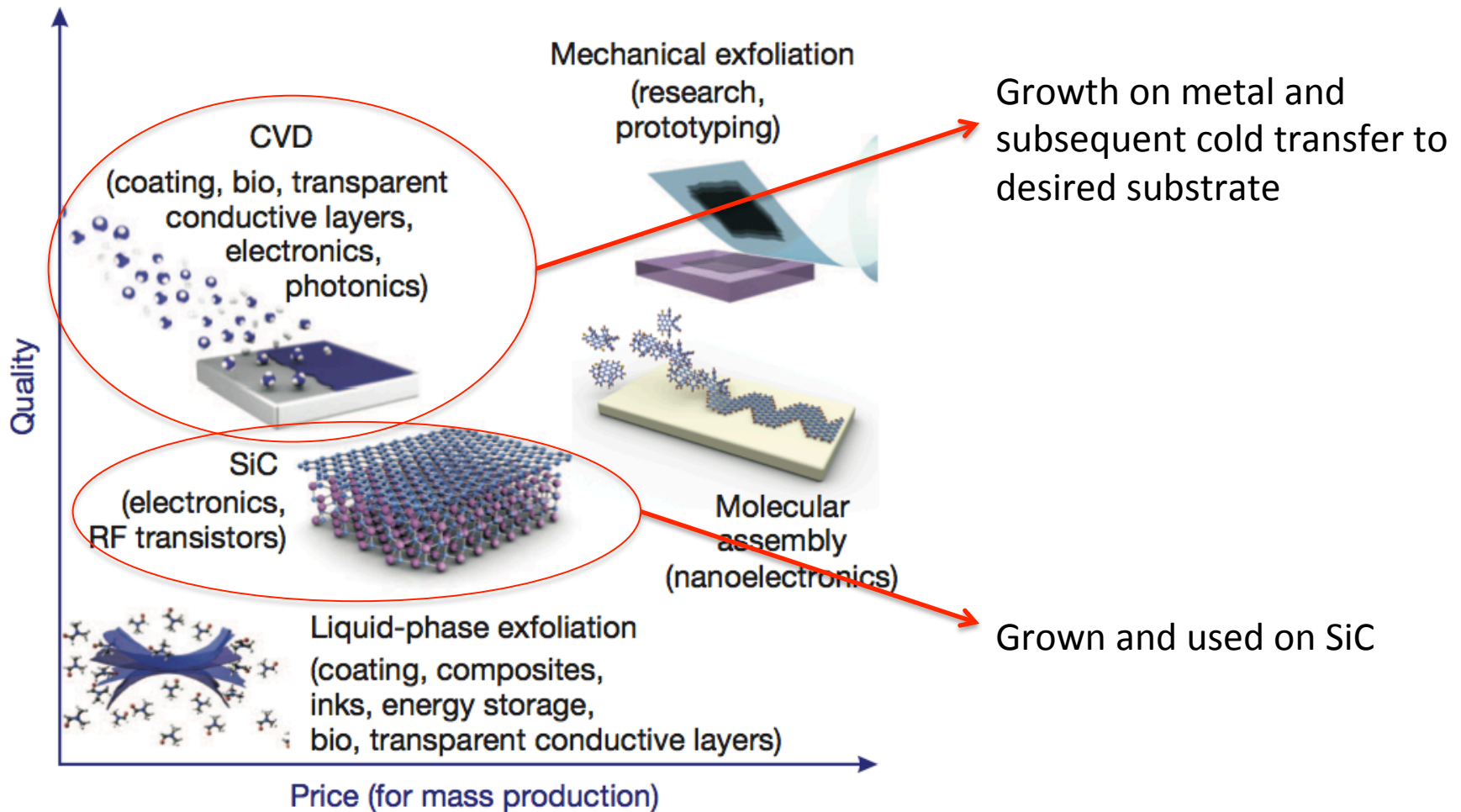
- Mechanical exfoliation
- Thermal decomposition of SiC
- CVD on transition metals



# Productions methods

Method	Crystallite size ( $\mu\text{m}$ )	Sample size (mm)	Mobility (ambient) ( $\text{cm}^2 \text{V}^{-1} \text{s}^{-1}$ )	Applications
Mechanical exfoliation	> 1000	> 1	> $2 \cdot 10^5$	Research
Chemical exfoliation	$\leq 0.1$	Infinite as overlapping flakes	100	Coating, paint/ink, composites, transparent conductive layers, energy storage, bioapplications
Chemical exfoliation via graphene oxide	$\sim 100$	Infinite as overlapping flakes	1	Coating, paint/ink, composites, transparent conductive layers, energy storage, bioapplications
CVD	1000	$\sim 1000$	10000	Photonics, nanoelectronics, transparent conductive layers, sensors, bioapplications
SiC	50	100	10000	High frequency transistors and other electronic devices

# Production methods



Novoselov et al. *A roadmap for graphene*, Nature **490** (2012)

# CVD graphene

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- Growth on metals:
  - Single crystals
  - Foils
  - Epitaxial layers
- Metals:
  - Cu (cheap, low carbon solubility, SLG)
  - Ni (cheap, high carbon solubility, MLG)
  - Rh, Ru, Pt, Au, Ir, etc. (expensive)
- Methods
  - Thermal CVD
  - PE CVD
  - Carbon segregation

# Graphene as a platform

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- 2D materials used with graphene:
  - h-BN (insulator)
  - MoS<sub>2</sub> (semiconductor)
  - Many more...
- CVD production of h-BN layers is possible.
- h-BN and graphene can be grown or transferred on top of each other.
- Hybrid h-BN/graphene layers can also be synthesized.

# Live STM studies of graphene growth

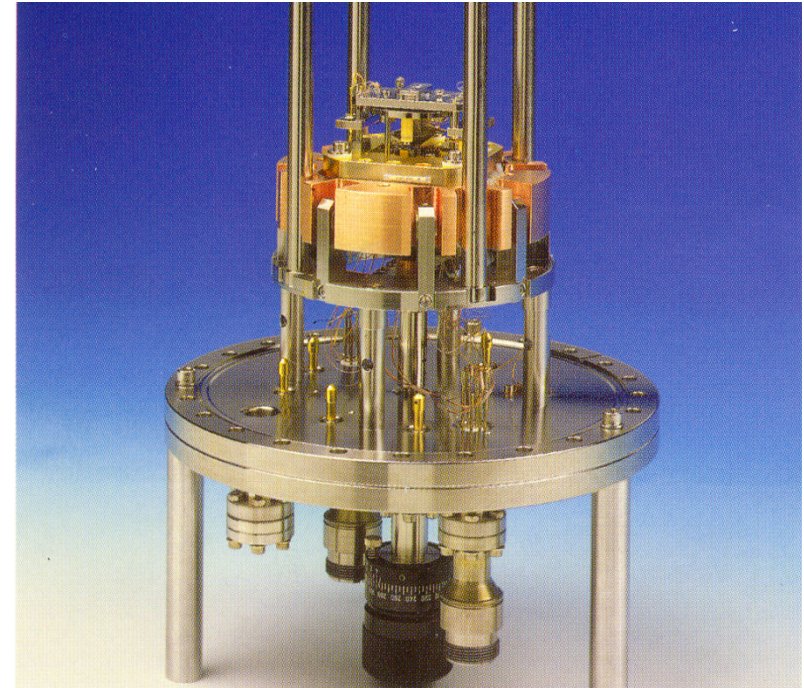
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## High speed

- **Speed:** *video-STM*  
0.01 – 25 frames/s  
(256x256 pixels) x2

## Variable temperature

- **Range:** - 50 K – 1300 K
- **Sweep:** - full T-range:  
same area in sight' over 300 K
- **'Secret':** - finite-element analysis



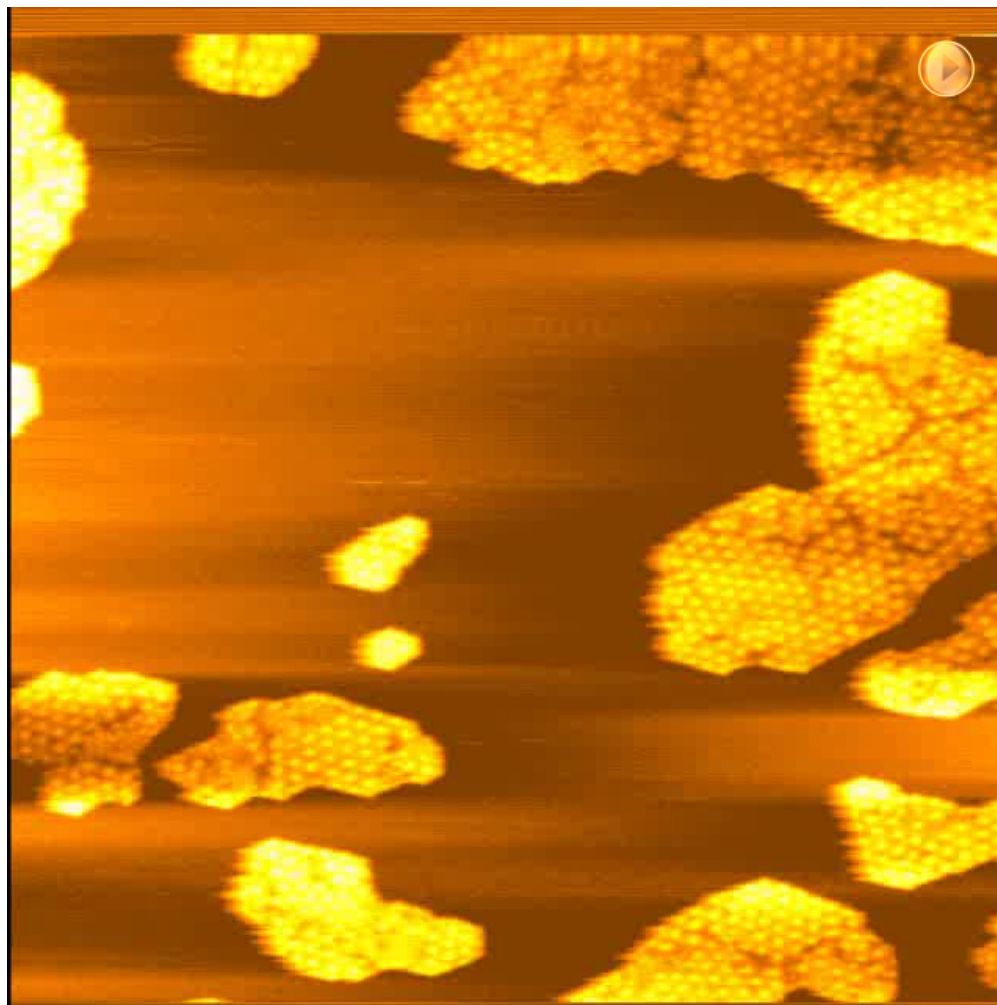
Hoogeman *et al.*, Rev.Sci.Instrum. **69** (1998) 2072  
M.J. Rost *et al.*, Rev.Sci.Instrum. **76** (2005) 053710



# Graphene growth on rhodium

*Start:* Rh(111) seeded with graphene at RT by  $C_2H_4$

*Movie:* further  $C_2H_4$  exposure at 975 K at  $3 \times 10^{-9} \sim 1 \times 10^{-8}$  mbar



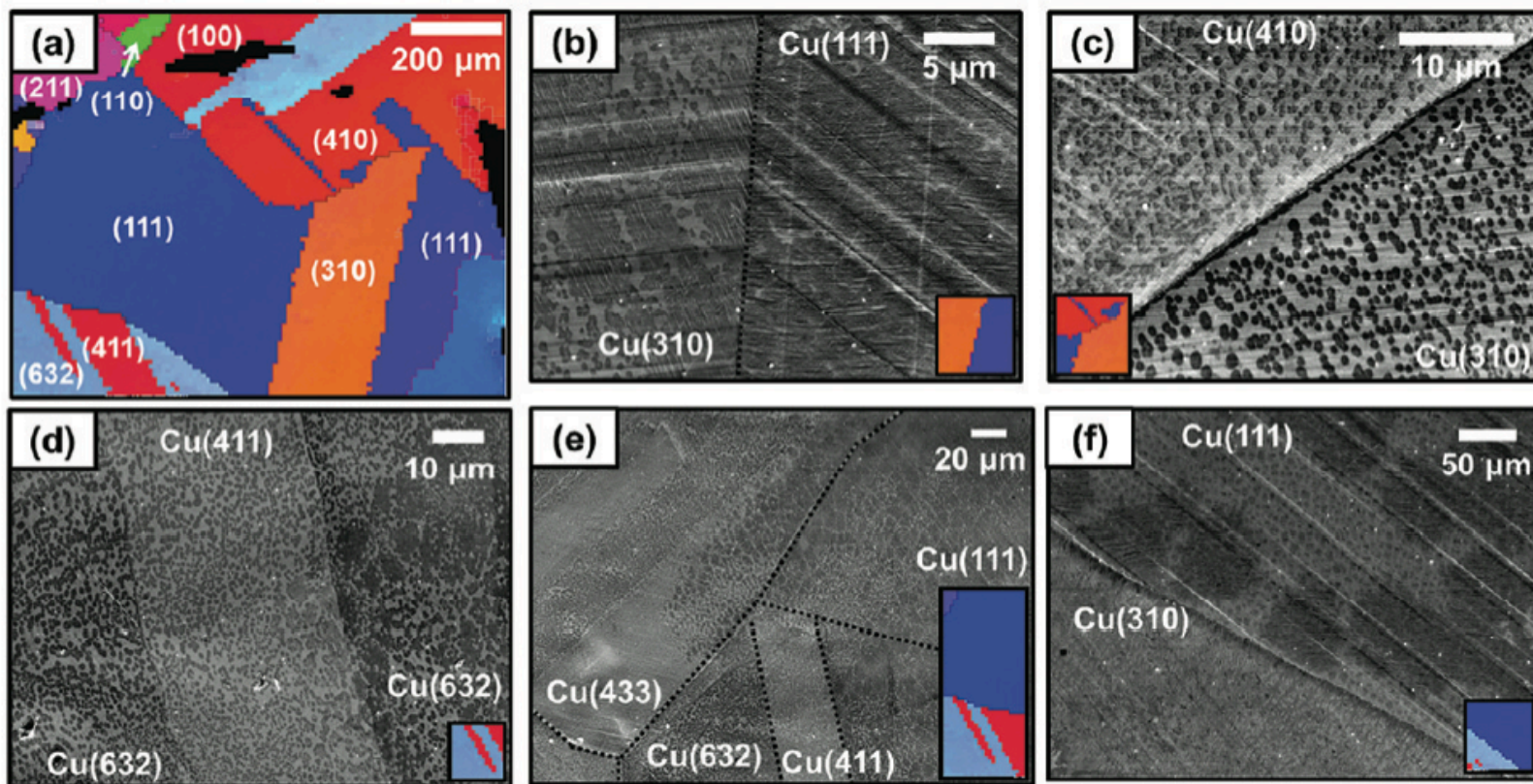
Real time: 76mins

$170 \times 170 \text{ nm}^2$

$I = 50 \text{ pA}$

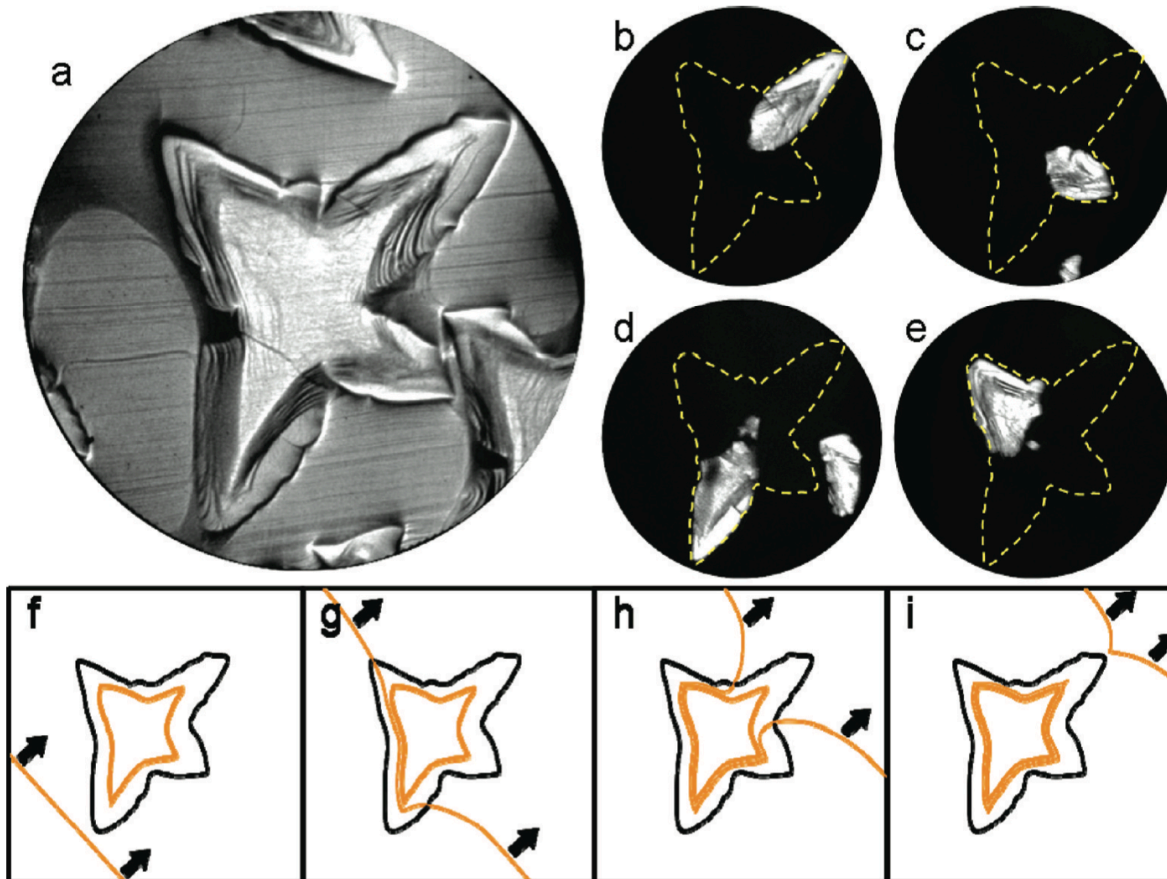
$V = -1.84 \text{ V}$

# Substrate orientation: or the problem with foil



Cu(111) gives highest quality graphene

# Crystalline Substrate Orientation



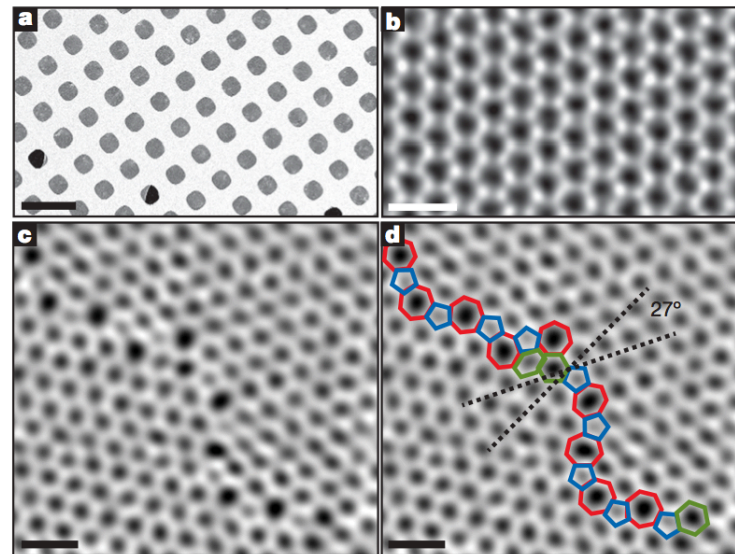
Cu(100) gives four different graphene domains in one graphene island

FIGURE 3. Bright (a) and dark field (b–e) LEEM images of a large graphene island on Cu(100) showing the spatial distribution of rotational variants. The graphene (01) direction is rotated by (b) 28°, (c) 2°, (d) 8°, and (e) 42°, relative to Cu(001) (FOV = 20  $\mu\text{m}$ , yellow dashes are the approximate island boundary). Cu step edge accumulation during growth results in a Cu hillock beneath the graphene island, as can be seen in (a). The hillock formation process is illustrated in (f–i).

# Grain boundary

## Grains and grain boundaries in single-layer graphene atomic patchwork quilts

Pinshane Y. Huang<sup>1\*</sup>, Carlos S. Ruiz-Vargas<sup>1\*</sup>, Arend M. van der Zande<sup>2\*</sup>, William S. Whitney<sup>2</sup>, Mark P. Levendorf<sup>3</sup>, Joshua W. Kevek<sup>4</sup>, Shivank Garg<sup>3</sup>, Jonathan S. Alden<sup>1</sup>, Caleb J. Hustedt<sup>5</sup>, Ye Zhu<sup>1</sup>, Jiwoong Park<sup>3,6</sup>, Paul L. McEuen<sup>2,6</sup> & David A. Muller<sup>1,6</sup>

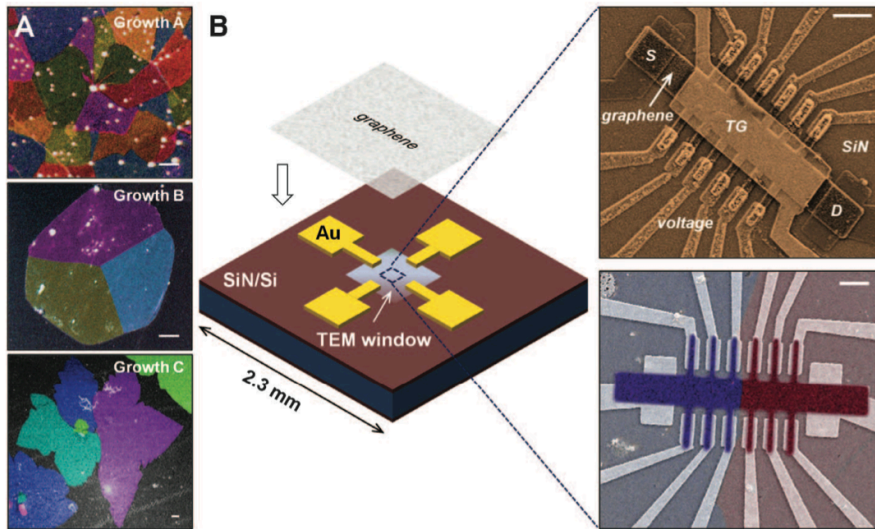


**Figure 1 | Atomic-resolution ADF-STEM images of graphene crystals.**  
**a**, Scanning electron microscope image of graphene transferred onto a TEM grid with over 90% coverage using novel, high-yield methods. Scale bar, 5  $\mu\text{m}$ .  
**b**, ADF-STEM image showing the defect-free hexagonal lattice inside a graphene grain. **c**, Two grains (bottom left, top right) intersect with a 27° relative rotation. An aperiodic line of defects stitches the two grains together.  
**d**, The image from **c** with the pentagons (blue), heptagons (red) and distorted hexagons (green) of the grain boundary outlined. **b–d** were low-pass-filtered to remove noise; scale bars, 5 Å.

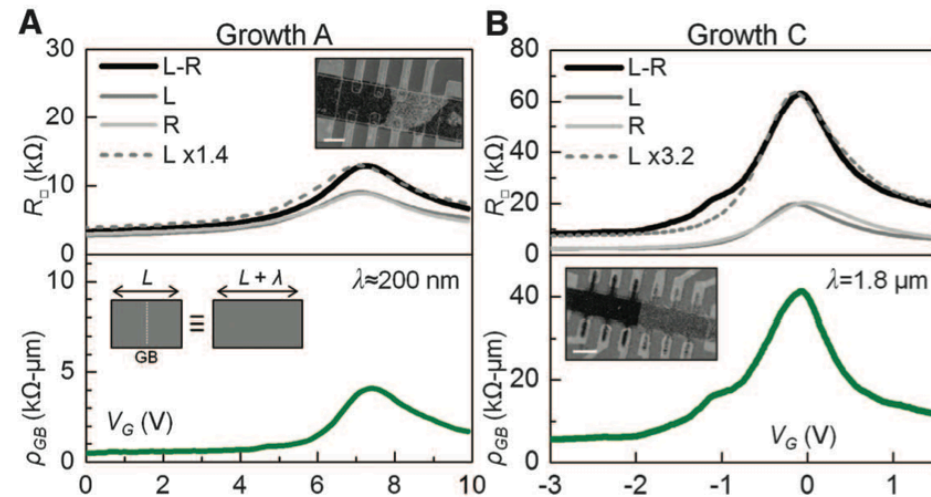
# Grain boundary

## Tailoring Electrical Transport Across Grain Boundaries in Polycrystalline Graphene

Adam W. Tsen,<sup>1</sup> Lola Brown,<sup>2</sup> Mark P. Levendorf,<sup>2</sup> Fereshte Ghahari,<sup>3</sup> Pinshane Y. Huang,<sup>1</sup> Robin W. Havener,<sup>1</sup> Carlos S. Ruiz-Vargas,<sup>1</sup> David A. Muller,<sup>1,4</sup> Philip Kim,<sup>3</sup> Jiwoong Park<sup>2,4\*</sup>



**Fig. 1.** (A) Composite false-color DF-TEM images of CVD graphene produced using three different growth conditions—A, B, and C—yielding average domain size  $D$  of 1, 10, and 50  $\mu\text{m}$ , respectively, in continuous films. (B) (Left) Schematic of specially fabricated TEM chip compatible with electron-beam lithography and electrical measurements. (Top right) SEM image of top-gated, graphene Hall bar device. (Bottom right) Overlaid SEM and DF-TEM images showing device crossing a single GB of two domains from growth C. Scale bars, 1  $\mu\text{m}$ .

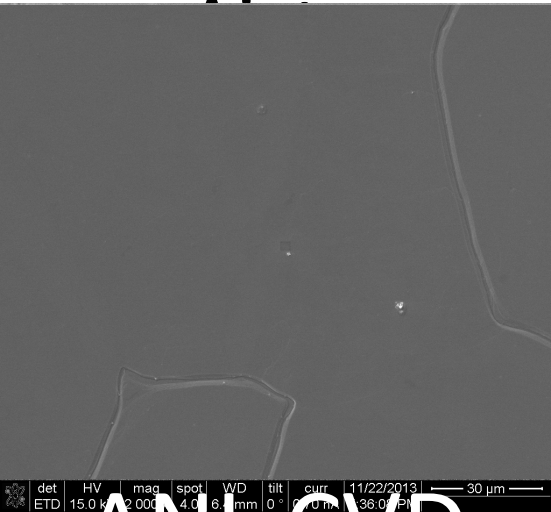


Growth method determines grain boundary resistivity

# Pilot production comparison

2 inch sapphire wafer + Cu + LPCVD graphene

4 inch Si wafer + Cu + PECVD graphene

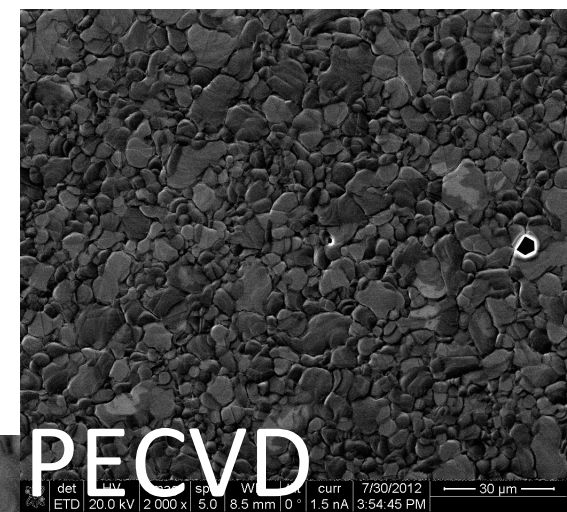


ANL CVD



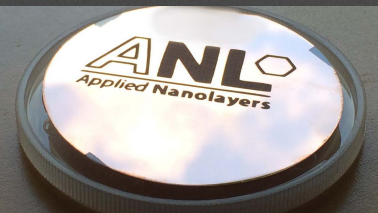
Foil

Commercial



PECVD

Commercial



lt	curr	11/22/2013	5 μm	HV	mag	spot	WD	tilt	curr	11/11/2013	5 μm	mag	spot	WD	tilt	curr	7/30/2012	5 μm
°	32 pA	6:21:43 PM		5.0 kV	10,000 x	4.0	6.5 mm	1 °	0.70 nA	6:05:29 PM		000 x	5.0	8.3 mm	0 °	0.26 nA	3:52:32 PM	

# Closing

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- Key to further graphene production improvement is the fundamental understanding of growth mechanisms.
- Establish a reliable supply chain for CVD graphene up to 200 mm substrates.
- Engineer for volume production.
- Fully automated QA toolchain.
  
- Contact: [r.van.rijn@appliednanolayers.com](mailto:r.van.rijn@appliednanolayers.com)